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# ELEC 402

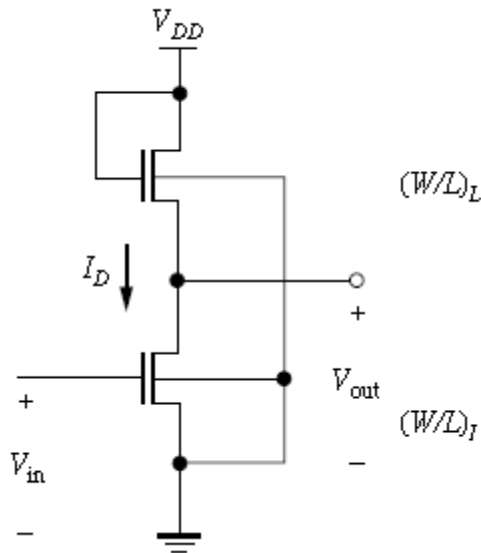
## Design of CMOS Inverter (Noise-margin-centric approach) Lecture 7

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# Saturated-enhancement-load Inverter



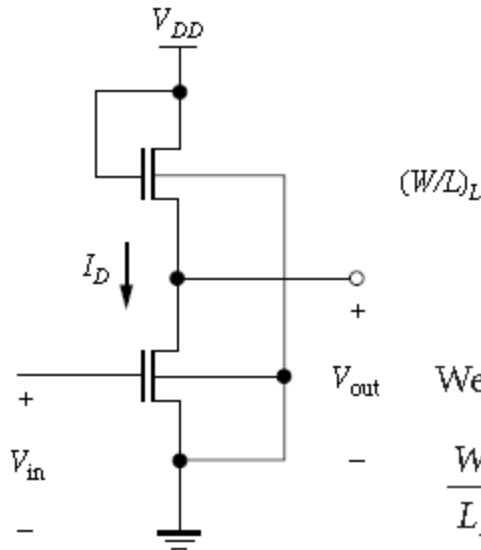
To alleviate the area problem we replace the resistor  
With a diode-connected transistor (always in saturation)  
This performance of this logic gate is affected by the ratio  
Of devices, hence called *ratioed* inverter

$$K_R = \frac{k_{\text{invert}}}{k_{\text{load}}} = \frac{k' (W/L)_I}{k' (W/L)_L} = \frac{(W/L)_I}{(W/L)_L}$$

The output voltage does not quite reach  $V_{DD}$   
(The Load device requires at least  $V_T$  drop on its  $V_{GS}$ )

$$\begin{aligned} V_{OH} &= V_{DD} - V_T(V_{OH}) \\ &= V_{DD} - [V_{T0} + \gamma(\sqrt{V_{OH} + 2|\phi_F|} - \sqrt{2|\phi_F|})] \end{aligned}$$

# Saturated-enhancement-load Inverter – cont'd



To derive the  $V_{OL}$  again it is important to find the proper region of operation for each transistor

$$I_{DL}(\text{lin}) = I_{DL}(\text{sat})$$

We can substitute in the current equations to obtain

$$\frac{W_f}{L_f} \frac{\mu_n C_{ox}}{\left(1 + \frac{V_{out}}{E_{CN} L_f}\right)} \left[ (V_{in} - V_{TH}) V_{out} - \frac{V_{out}^2}{2} \right] = \frac{W_L \mu_{sat} C_{ox} (V_{DD} - V_{out} - V_{TL})^2}{(V_{DD} - V_{out} - V_{TL}) + E_{CN} L_L}$$

Note that  $V_{in}$  should be the output of previous stage (ideally  $V_{DD} - V_T$ ), however, to keep Things simple we occasionally assume  $V_{in} = V_{DD}$

# Example – Why is it a *ratioed* logic gate

## Design of Saturated Load Inverter

### Problem:

Design the saturated enhancement load inverter of Figure 4.10a such that it delivers a low output voltage of  $V_{OL} = 0.1$  V when the input is  $V_{DD}$ . Assume a  $0.13 \mu\text{m}$  technology, with  $L = 100$  nm and let the pull-up device be of unit size. Use the parameters

$$\mu_n = 270 \text{ cm}^2/\text{V}\cdot\text{s}, \quad C_{ox} = 1.6 \text{ } \mu\text{F}/\text{cm}^2, \quad V_{T0} = 0.4 \text{ V}, \quad V_{DD} = 1.2 \text{ V}$$

$$E_{CN}L = 0.6 \text{ V}, \quad v_{sat} = 8 \times 10^6 \text{ cm/s}, \quad \gamma = 0.2 \text{ V}^{1/2}$$

Use the current equation for the pull-down in the linear region and the pull-up in the saturation region.

$$\frac{W_I}{L_I} \frac{\mu_n C_{ox}}{\left(1 + \frac{V_{out}}{E_{CN}L_I}\right)} \left[ (V_{in} - V_n)V_{out} - \frac{V_{out}^2}{2} \right] = \frac{W_L v_{sat} C_{ox} (V_{DD} - V_{out} - V_{TL})^2}{(V_{DD} - V_{out} - V_{TL}) + E_{CN}L_L}$$

We can eliminate  $C_{ox}$  and then set  $V_{in} = V_{DD}$  (we should really set it to  $V_{OH}$  but we keep things simple in this problem) and  $V_{out} = V_{OL}$ :

$$\therefore \frac{W_I}{L_I} \frac{\mu_n}{\left(1 + \frac{V_{OL}}{E_{CN}L_I}\right)} \left[ (V_{DD} - V_n)V_{OL} - \frac{V_{OL}^2}{2} \right] = \frac{W_L v_{sat} (V_{DD} - V_{OL} - V_{TL})^2}{(V_{DD} - V_{OL} - V_{TL}) + E_{CN}L_L}$$

# Saturated-enhancement-load Inverter – cont'd

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Since we know that the output voltage is  $V_{OL} = 0.1$  V, we can compute the correct  $V_T$ :

$$\begin{aligned} V_T &= [V_{T0} + \gamma(\sqrt{V_{SB} + 2|\phi_F|} - \sqrt{2|\phi_F|})] \\ &= [0.4 + 0.2(\sqrt{0.1 + 2|-0.44|} - \sqrt{2|-0.44|})] \\ &= 0.4 + 0.2(\sqrt{0.1 + 0.88} - \sqrt{0.88}) \\ &= 0.41 \text{ V} \end{aligned}$$

The degree of body effect is small, as one would expect with a body-bias of 0.1 V. We can substitute the known quantities and solve for the transistor sizes:

$$\begin{aligned} \therefore \frac{W_I}{0.1(10^{-4})\text{cm}} \frac{(270 \text{ cm}^2/\text{V}\cdot\text{s})}{(1 + (0.1/0.6))} \left[ (1.2 - 0.4)0.1 - \frac{0.1^2}{2} \right] \\ = \frac{W_L(8 \times 10^6 \text{ cm/s})(1.2 - 0.1 - 0.41)^2}{(1.2 - 0.1 - 0.41) + 0.6} \end{aligned}$$

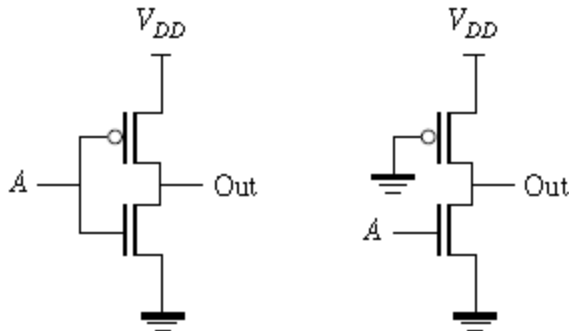
$$\therefore K_R = \frac{W_I}{W_L} = \frac{2.95}{1.75} = 1.7$$

If  $W_L = 100$  nm, then  $W_I = 170$  nm.

# Pseudo-NMOS Inverter

To address issues with NMOS loads

- Saturated NMOS load, a.k.a diode connected load, has degraded  $V_{OH}$
- Linear NMOS load requires two supplies and extra area/interconnects
- CMOS gates require multiple loads for multi fanin inputs (?)



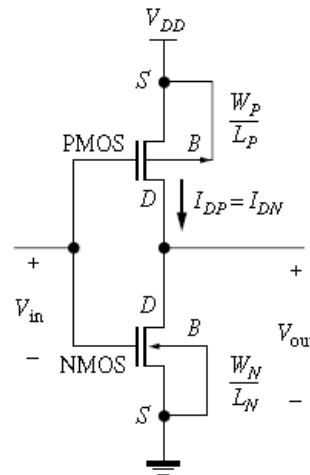
Solves the abovementioned problems, However

- *Ratioed* inverter, i.e.  $V_{OL}$  a function of two device ratios
- Large  $T_{PLH}$  (why?)

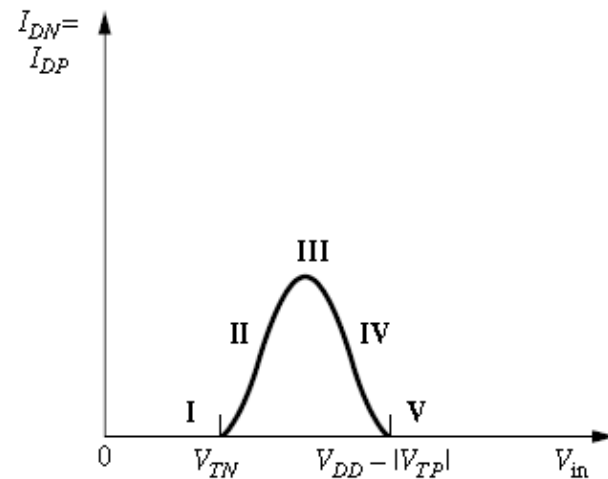
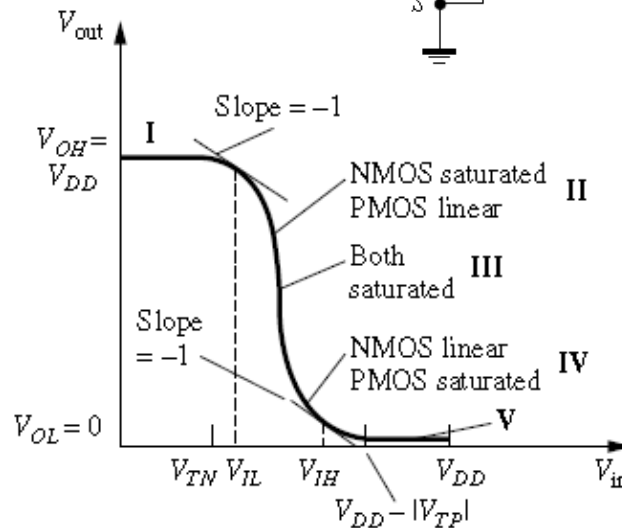
$$I_{DP}(\text{sat}) = I_{DN}(\text{lin})$$

$$\frac{W_P \mu_{sat} C_{ox} (V_{DD} - |V_{TP}|)^2}{(V_{DD} - |V_{TP}|) + E_{CP} L_P} = \frac{W_N}{L_N} \frac{\mu_n C_{ox}}{\left(1 + \frac{V_{OL}}{E_{CN} L_N}\right)} \left[ (V_{DD} - V_{TN})(V_{OL}) - \frac{(V_{OL})^2}{2} \right] \Rightarrow V_{OL} = \frac{I_{DP}(\text{sat})}{k_N (V_{DD} - V_{TN})}$$

# CMOS Inverter

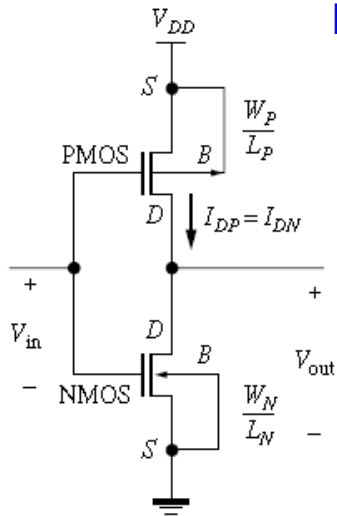


- Address both issues of area and static power consumption
- Load that is complementary to the inverting device
- 5 distinct regions of operation can be detected



# CMOS Inverter

Region III: NMOS saturation, PMOS saturation



$V_S$  falls in this region (why?)

$$\frac{W_N \mu_{sat} C_{ox} (V_S - V_{TN})^2}{(V_S - V_{TN}) + E_{CN} L_N} = \frac{W_P \mu_{sat} C_{ox} (V_{DD} - V_S - |V_{TP}|)^2}{(V_{DD} - V_S - |V_{TP}|) + E_{CP} L_P}$$

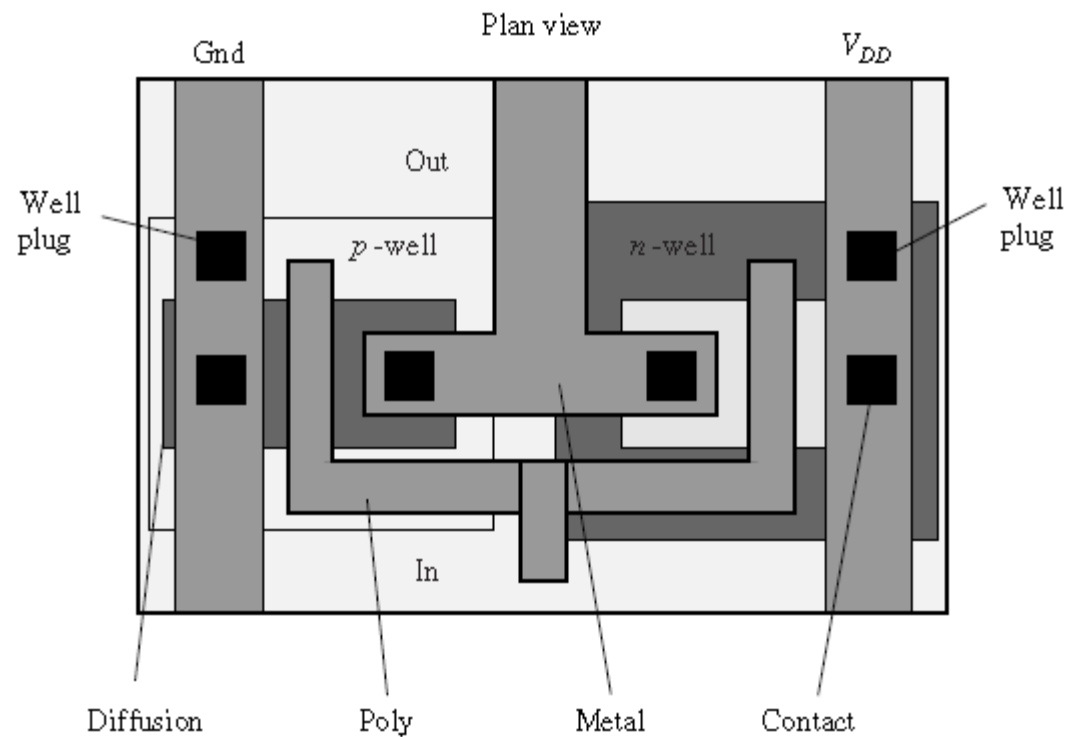
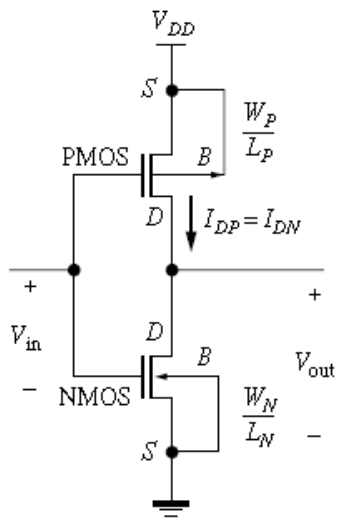
(Board Notes)

$$V_S = \frac{V_{DD} - |V_{TP}| + \chi V_{TN}}{1 + \chi}$$

$$\chi = \sqrt{\frac{\frac{W_N}{E_{CN} L_N}}{\frac{W_P}{E_{CP} L_P}}} = \sqrt{\frac{\mu_n W_N}{\mu_p W_P}}$$



# CMOS Inverter - Layout



Note Minimum size, well-plugs, design rules